L Number	Hits	Search Text	DB	Time stamp
/	720	tungsten with silane	USPAT;	2002/11/12 13:12
	729	tungsten with silane	US-PGPUB	
_	4.6	tungsten with silane with dop\$3	USPAT;	2002/11/12 13:12
8	46	tungsten with Silane with dopps	US-PGPUB	2002, 22, 22
1		doné?	USPAT;	2002/11/12 13:12
9	1368	tungsten with silicon with dop\$3	US-PGPUB	2002/11/12 10:11
			USPAT;	2002/11/12 13:13
10	1284	tungsten with silicon with doped	·	2002/11/12 13:13
			US-PGPUB	2002/11/12 13:13
11	4	tungsten with silicon with doped with	USPAT;	2002/11/12 13.13
		strength	US-PGPUB	0000/11/10 17:51
12	2561	(427/250-253).CCLS.	USPAT;	2002/11/12 17:51
			US-PGPUB	2222 /11 /12 15 20
13	11	fuller.xa. with eric	USPAT;	2002/11/12 15:09
			US-PGPUB	0000 (11 (10 15 11
14	13	((427/250-253).CCLS.) and hydroxide with	USPAT;	2002/11/12 15:11
		substrate	US-PGPUB	
15	37	((427/250-253).CCLS.) and hydroxide with	USPAT;	2002/11/12 15:12
		(substrate or surface)	US-PGPUB	
16	8	(((427/250-253).CCLS.) and hydroxide with	USPAT;	2002/11/12 15:23
	_	(substrate or surface)) and (silane or	US-PGPUB	
1		Si?sub.4)		
17	195	silane with hydroxide with surface	USPAT;	2002/11/12 15:23
<b>+</b> ′	175	<u> </u>	US-PGPUB	
18	28	(silane with hydroxide with surface) and	USPAT;	2002/11/12 15:28
10	20	(metal tungsten) with film	US-PGPUB	
10	159	semiconductor with substrate with	USPAT;	2002/11/12 15:28
19	139	hydroxide	US-PGPUB	
	14	(semiconductor with substrate with	USPAT;	2002/11/12 15:31
20	14	hydroxide) and silane	US-PGPUB	
	740	metal with (film coating) with hydroxide	USPAT;	2002/11/12 15:32
21	742	with (substrate surface)	US-PGPUB	
	11	metal with (film coating) with hydroxide	USPAT;	2002/11/12 15:32
22	11	with (substrate surface) with silane	US-PGPUB	2002, 12, 12
		with (substrate surface) with Silahe	USPAT;	2002/11/12 17:32
35	17	((427/250-253).CCLS.) and metal adj	US-PGPUB	2002/11/12 1:132
		hydroxide	USPAT;	2002/11/12 17:48
36	37	((427/250-253).CCLS.) and (substrate or	US-PGPUB	2002/11/12 17:40
		surface) with hydroxide		2002/11/12 17:49
37	0	1 2	USPAT;	2002/11/12 17.49
		substrate)	US-PGPUB	2002/11/12 17:50
38	9	hydroxilated	USPAT;	2002/11/12 17:30
			US-PGPUB	2002/11/12 17:51
39	775	silane with hydroxide	USPAT;	2002/11/12 17:51
			US-PGPUB	0000/11/10 17 51
40	1	((427/250-253).CCLS.) and (silane with	USPAT;	2002/11/12 17:51
		hydroxide)	US-PGPUB	1 414 405 15 20
-	4406	(427/584-587,248.1,250-253).CCLS.	USPAT;	2002/11/05 16:38
			US-PGPUB	2220/11/25 15 12
-	1588	(427/255.23-255.26,255.28,255.39-255.392,25	5 USPACCLS.	2002/11/05 16:43
1		,	US-PGPUB	0000/11/05 15 15
!	8		USPAT;	2002/11/05 17:45
		adj layer adj deposition)	US-PGPUB	
_	1		USPAT;	2002/11/05 17:11
			US-PGPUB	
, <b>-</b>	35	((427/250-253).CCLS.) and sequen\$6 with	USPAT;	2002/11/05 17:25
		(CVD or chemical adj vapor adj deposition)	US-PGPUB	
, <u>-</u>	55	((427/250-253), CCLS.) and altern\$6 with	USPAT;	2002/11/05 17:25
		(CVD or chemical adj vapor adj deposition)	US-PGPUB	
	. 7		USPAT;	2002/11/05 17:44
ļ	,	or ("4851095") or ("4935661") or	US-PGPUB	
		("5356673") or ("5916365")).PN.		
_	1	("6200893").PN.	USPAT;	2002/11/05 17:44
_	1	1 0200033 /	US-PGPUB	
	046	ald or atomic adj layer adj deposition	USPAT;	2002/11/05 17:45
_	946	atu of acomic adj tayer adj deposicion	US-PGPUB	
		(ald or atomic adj layer adj deposition)	USPAT;	2002/11/05 17:45
_	567		US-PGPUB	1 2002, 11, 00 1.11
İ	`	and metal	USPAT;	2002/11/05 17:45
_	94	, ,	US-PGPUB	2002/11/03 17:10
		with metal		2002/11/05 17:46
-	13		USPAT;	2002/11/03 17.10
l		with metal) and @ad<=19990315	US-PGPUB	L

Search History 11/12/02 6:55:07 PM Page 1